

# POKHARA UNIVERSITY

Level: Bachelor Semester: Fall Year : 2021  
 Programme: BE Full Marks: 100  
 Course: Electrical Engineering Materials Pass Marks: 45  
 Time : 3hrs.

*Candidates are required to give their answers in their own words as far as practicable.*

*The figures in the margin indicate full marks.*

**Attempt all the questions.**

1. a) Derive the wave function for an electron confined in the infinite potential well. 8  
 b) Define the term electrons drift velocity and mobility. How are they related? Show that the conductivity of electrons with in metallic conductor is product of charge density and mobility. 7
2. a) Show that ionic conduction in liquid decreases with increase in temperature and increases with increases in electric field. 7  
 b) What are different types of polarization in dielectric medium? Explain orientational polarization in detail. 8
3. a) Explain the Hysteresis loop and define hard and soft magnetic materials. 7  
 b) Derive the expression for density state per unit volume and per unit energy. 8
4. a) In intrinsic Semiconductor, Prove that the Fermi Level lies at the center of valence band and conduction band. 8  
 b) A heavily doped p-side with acceptor concentration of  $10^{18} \text{ cm}^{-3}$  is connected to n-side with donor concentration of  $10^{16} \text{ cm}^{-3}$ . Calculate the built in potential and depletion width. 7  
 Assume  $T = 300 \text{ K}$  and  $n_i = 1.45 \times 10^{10} \text{ cm}^{-3}$ .
5. a) Derive the Ideal diode Equation for PN junction. 8  
 b) Calculate the resistance of pure silicon cubic crystal of  $1 \text{ cm}^3$  at room temperature. What will be the resistance of the cube when it is doped with 1 arsenic in  $10^9$  Silicon atoms and 1 boron atom per billion silicon atoms? Atomic concentration of silicon is  $5 \times 10^{22} \text{ cm}^{-3}$ , intrinsic concentration  $n_i = 1.45 \times 10^{10} \text{ cm}^{-3}$ . Assume the mobilities of electron and hole are  $1350$  and  $450 \text{ cm}^2 \text{ V}^{-1} \text{ s}^{-1}$ . 7

6. a) Explain the ion implantation process with a neat sketch. 7  
 b) A parallel plate capacitor has an area of  $20 \text{ cm}^2$  and a separation of  $0.5 \text{ mm}$ . The space between the plates is filled with polyethylene. An alternative voltage with amplitude of  $12 \text{ V}$  is applied at a frequency of  $1.5 \text{ MHz}$ . At this frequency, the real part of the relative permittivity is  $2.25$  and the loss tangent is  $4 \times 10^{-4}$ . Calculate the energy dissipated per second. 8
7. Write short notes on: (Any two) 2×  
 a) Degenerate and Non-degenerate Semiconductor 5  
 b) Fermi Dirac distribution function  
 c) Diffusion and depletion layer capacitance